| | , | | DB | Timo stama |
|----------|--------------|---|---------------------|-----------------------------|
| L Number | Hits | Search Text | DB | Time stamp 2003/12/31 13:23 |
| | 167931 | control\$2 near2 valve | USPAT; US-PGPUB | |
| 2 | 496 | charge near2 surface near2 (sample mask wafer workpiece) | USPAT; US-PGPUB | 2003/12/31 13:25 |
| 3 | 18 | (control\$2 near2 valve) and (charge near2 surface near2 (sample mask wafer workpiece)) | USPAT; US-PGPUB | 2003/12/31 13:25 |
| 4 | 20733 | charge near2 (monitor sens\$3 detect\$3) | USPAT; US-PGPUB | 2003/12/31 13:25 |
| 5 | 1923 | <pre>(charge near2 (monitor sens\$3 detect\$3)) and rising</pre> | USPAT; US-PGPUB | 2003/12/31 13:25 |
| 6 | 797 | ((charge near2 (monitor sens\$3 detect\$3)) and rising) and (sample mask wafer workpiece) | USPAT; US-PGPUB | 2003/12/31 13:28 |
| 7 | 28 | (control\$2 near2 valve) and ((charge near2 (monitor sens\$3 detect\$3)) and rising) and (sample mask wafer workpiece)) | USPAT; US-PGPUB | 2003/12/31 13:26 |
| .8 | 117 | ((charge near2 (monitor sens\$3 detect\$3)) and rising) and wafer | USPAT; US-PGPUB | 2003/12/31 13:34 |
| 9 | 24306 | wafer near2 process | USPAT; US-PGPUB | 2003/12/31 13:34 |
| 10 | 289 | <pre>(charge near2 (monitor sens\$3 detect\$3)) and (wafer near2 process)</pre> | USPAT; US-PGPUB | 2003/12/31 13:43 |
| 11 | 18 | <pre>(control\$2 near2 valve) and ((charge near2 (monitor sens\$3 detect\$3)) and (wafer near2 process))</pre> | USPAT; US-PGPUB | 2003/12/31 13:34 |
| 12 | 217 | ESD and (wafer near2 process) | USPAT; US-PGPUB | 2003/12/31 13:50 |
| 13 | 186 | (determin\$2 compar\$2) near2 charge and (wafer near2 process) | USPAT; US-PGPUB | 2003/12/31 13:52 |
| 14 | 3 | (control\$2 near2 valve) and ((determin\$2 compar\$2) near2 charge and (wafer near2 process)) | USPAT; US-PGPUB | 2003/12/31 13:51 |
| 15 | 309 | (determin\$2 compar\$2 measur\$2) near2 charge and (wafer near2 process) | USPAT; US-PGPUB | 2003/12/31 14:15 |
| 16 | 107 | ((determin\$2 compar\$2 measur\$2) near2 charge and (wafer near2 process)) and (valve rising) | USPAT; US-PGPUB | 2003/12/31 13:53 |
| 17 | 182 | (determin\$2 compar\$2 measur\$2) near2 charge and drying near2 process | USPAT; US-PGPUB | 2003/12/31 14:38 |
| 18 | 14 | ((determin\$2 compar\$2 measur\$2) near2 charge and drying near2 process) and wafer | USPAT; US-PGPUB | 2003/12/31 14:23 |
| 19 | 2210 | exceed\$2 near2 charge | USPAT; US-PGPUB | 2003/12/31 14:23 |
| 20 | 11 | (wafer near2 process) and (exceed\$2 near2 charge) | USPAT; US-PGPUB | 2003/12/31 14:29 |
| 21 | 151 | drying and (exceed\$2 near2 charge) | USPAT; US-PGPUB | 2003/12/31 14:30 |
| 22 | 2 | (drying and (exceed\$2 near2 charge)) and wafer | USPAT; US-PGPUB | 2003/12/31 14:30 |
| 23 | 0 | spin near2 drying and (exceed\$2 near2 charge) | USPAT; US-PGPUB | 2003/12/31 14:30 |
| 24 | 64 | spin and (exceed\$2 near2 charge) | USPAT; US-PGPUB | 2003/12/31 14:30 |
| 25 | 5 | (spin and (exceed\$2 near2 charge)) and wafer | USPAT; US-PGPUB | 2003/12/31 14:31 |
| 27 | 0 | (exceed\$2 near2 charge) and (sensor near2 arm and wafer near2 process) | USPAT; US-PGPUB | 2003/12/31 14:32 |
| 26 | 133 | sensor near2 arm and wafer near2 process | USPAT; US-PGPUB | 2003, 12/31 14:35 |
| 28 | 125 | dispens\$2 and (exceed\$2 near2 charge) | USPAT; US-PGPUB | 2003, 12/31 14:35 |
| 29 | 4 | (dispens\$2 and (exceed\$2 near2 charge)) and wafer | USPAT; ,US-PGPUB | 2003/12/31 14:35 |
| 30 | 91 | (determin\$2 compar\$2) near2 charge and drying near2 process | USPAT; US-PGPUB | 2003/12/31 14:38 |